

ABSTRACT OF THE DISCLOSURE

SUBSTRATE CLEANING APPARATUS, SUBSTRATE CLEANING METHOD AND SUBSTRATE PROCESSING APPARATUS

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A substrate cleaning apparatus for cleaning a substrate while rotating the substrate and placing a cleaning member in contact with the rotating substrate is disclosed. The substrate cleaning apparatus comprises : a self-cleaning member mounted to an arm supporting the cleaning member, the self-cleaning member being configured to come into
10 contact with the cleaning member to perform self-cleaning of the cleaning member; and a moving mechanism mounted to the arm supporting the cleaning member, the moving mechanism being configured to move the self-cleaning member between a position where the self-cleaning member is in contact with the cleaning member and a position where the self-cleaning member is separated from the cleaning member.

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FIG. 10